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064441.0207

PATENT APPLICATION
09/784,800

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REMARKS

As requested by Examiner Dunn, Applicants submit the topics that Applicants would like to discuss and proposed remarks for the Examiner's review in preparation for a telephone interview to be conducted on September 6, 2005.

Objections to the Claims

In the Office Action dated May 19, 2005, the Examiner objected to Applicants' amendments in the response filed on February 9, 2005 as adding new matter into the disclosure. Specifically, the Examiner states that "[t]he specification fails to teach that the transmitted light passes through the photomask, then through the thin film and then to the wafer, and fails to teach the light diffracted by the photomask or the projected image generated from the photomask will pass the thin film again. This is completely in contradiction to the photolithographic process. The specification explicitly teaches that the photomask is on the wafer and it is impossible for the light to pass through the photomask and then through the thin film then onto the wafer, (please see Figure 3)." (Office Action, Pages 2-3). Applicants submit that no new matter was added, that the claims are not in contradiction to the photolithographic process and that the Examiner's statement regarding the photomask being on the wafer is wrong.

- Figure 3 is a cross sectional view of a photomask assembly that illustrates a pellicle mounted on a photomask. The figure does not illustrate a photomask on a wafer.
- The specification teaches that a lens is used to project an image from the photomask onto a wafer. (Specification, Pages 4-5). The specification additionally teaches that the pellicle may be placed between the photomask and the imaging lens. (Specification, Page 10). Therefore, the specification teaches that the light diffracted by the photomask will pass through the thin film.

Rejections under 35 U.S.C. § 112

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In the Office Action dated May 19, 2005, the Examiner rejected Claim 7 under 35 U.S.C. § 112, first paragraph. Specifically, the Examiner states that the phrase "projection of the diffracted portion of light . . . increase the resolution of the image" is not enabled by the disclosure because "[t]he resolution of a projected image therefore is implicitly defined at least in part by the size of spatial information of the photomask, but not by the projection of certain portion of the light." (Office Action, Page 4). In an Office Action dated December 10, 2004, the Examiner stated that the phrase "the resolution of the image . . . being defined at least in part by the projected spatial information" was "confusing and indefinite since it is not clear what is this spatial information and how can the resolution be defined by the spatial information." (Office Action, Page 4). These statements are completely inconsistent.

In the Office Action dated May 19, 2005, the Examiner rejected Claims 7, 17 and 26 under 35 U.S.C. § 112, first paragraph. Specifically, the Examiner states that "the phrase 'light transmitted . . . through opening in the photomask through the thin film onto the wafer . . . a portion of the transmitted light is diffracted by the photomask opening and passes through the thin film' . . . is completely wrong. . . . The light diffracted by the photomask will not pass through the thin film again rather the diffracted light will proceed to the wafer." (Office Action, Page 4). As stated above, the pellicle may be located between the photomask and the imaging lens used to project an image on the wafer. (Specification, Page 10). Therefore, the diffracted light will pass through the thin film.

Finally, the Examiner rejected Claim 17 under 35 U.S.C. § 112, first paragraph because "[t]he specification only enables the off-axis light at certain degrees of incidence to have transmission approximates 99% of the light but not to all of the off-axis lights or not to any off-axis light at any incident angle." (Office Action, Page 4). Claim 17 recites the limitation of an "amorphous fluoropolymer thin film operable to transmit approximately ninety-nine percent (99%) of off-axis light at a particular wavelength." The claim does not recite transmission of all off-axis light at any incident angle. The claim is enabled by the specification. (See Specification, Figure 5)

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CONCLUSION

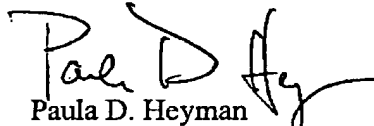
Applicants appreciate the Examiner's careful review of the application. For the foregoing reasons, Applicants respectfully request reconsideration of Claims 7, 9-14, 16-24 and 26-30.

Applicants believe there are no additional fees due, however, the Commissioner is hereby authorized to charge any additional fees or credit any overpayment to Deposit Account No. 50-2148 of Baker Botts L.L.P.

If there are any matters concerning this Application that may be cleared up in a telephone conversation, please contact Applicants' attorney at 512.322.2581.

Respectfully submitted,

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Date: Sept 2, 2005

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